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TO THE UNITED STATES PATENT AND TRADEMARK OFFICE

Patent Application Serial No. 10/655,699
Filing Date September 5, 2003
Inventor Garo Derderdian et al.
Assignee Micron Technology, Inc.
Group Art Unit 2812
Examiner Unknown
Attorney Docket No. MI22-2307
Customer No. 021567
Title: Methods of Depositing a Silicon Dioxide Comprising Layer in the Fabrication of Integrated Circuitry, and a Method of Forming Trench Isolation in the Fabrication of Integrated Circuitry

TO: Commissioner for Patents
P. O. Box 1450
Alexandria, VA 22313-1450

STATUS INQUIRY

1. More than eighteen (18) months have passed since the filing of this Utility Application on September 5, 2003.
2. Kindly advise the undersigned of the present status of this patent application, in particular, when the undersigned might reasonably expect a first examination. A Status Inquiry Reply is provided as the second page hereof. Please complete and then fax said second page/reply to the facsimile number indicated thereon.

Dated: 5-6-05
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(Status Inquiry--page 1 of 2)

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RE: PATENT APPLICATION SERIAL NO. 10/655,699:

- ☐ FURTHER EXAMINATION OR ALLOWANCE IS EXPECTED TO BE
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